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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/675,996	10/02/2003	Hiroyuki Koide	00862.023261.	7786	
5514	7590 04/20/2005		EXAM	EXAMINER	
FITZPATRICK CELLA HARPER & SCINTO 30 ROCKEFELLER PLAZA			JONES, JUDSON		
	K, NY 10112		ART UNIT	PAPER NUMBER	
			2834		
			DATE MAILED: 04/20/2005	DATE MAILED: 04/20/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

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		Application No.	Applicant(s)	
		10/675,996	KOIDE, HIROYUKI	
i.	Office Action Summary	Examiner	Art Unit	
		Judson H. Jones	2834	
Perio	The MAILING DATE of this communication od for Reply	n appears on the cover sheet w	vith the correspondence address	S
A T -	A SHORTENED STATUTORY PERIOD FOR RITHE MAILING DATE OF THIS COMMUNICATION Extensions of time may be available under the provisions of 37 CF after SIX (6) MONTHS from the mailing date of this communication if the period for reply specified above is less than thirty (30) days, if NO period for reply is specified above, the maximum statutory preailure to reply within the set or extended period for reply will, by so Any reply received by the Office later than three months after the earned patent term adjustment. See 37 CFR 1.704(b).	ON. FR 1.136(a). In no event, however, may a n. a reply within the statutory minimum of th eriod will apply and will exoire SIX (6) MO statute, cause the application to become A	reply be timely filed irty (30) days will be considered timely. NTHS from the mailing date of this communi NBANDONED (35 U.S.C. § 133).	ication.
Statı	us			
1) Responsive to communication(s) filed on			
	· · · ·	This action is non-final.		
	Since this application is in condition for all	•	tters, prosecution as to the mer	its is
	closed in accordance with the practice und	·	•	
Disp	osition of Claims			
5 6 7	Claim(s) 1-10 is/are pending in the application 4a) Of the above claim(s) is/are with Claim(s) is/are allowed. Claim(s) 1,2,6 and 8-10 is/are rejected. Claim(s) 3-5 and 7 is/are objected to. Claim(s) are subject to restriction a	ndrawn from consideration.	•	
Appi	lication Papers	·		
10	P)☐ The specification is objected to by the Example The drawing(s) filed on <u>02 October 2003</u> is Applicant may not request that any objection to Replacement drawing sheet(s) including the ∞ 1)☐ The oath or declaration is objected to by the	s/are: a)⊠ accepted or b)□ o the drawing(s) be held in abeya orrection is required if the drawin	ance. See 37 CFR 1.85(a). g(s) is objected to. See 37 CFR 1.	` '
Prio	rity under 35 U.S.C. § 119			
12	2) Acknowledgment is made of a claim for for a) All b) Some * c) None of: 1. Certified copies of the priority docur 2. Certified copies of the priority docur 3. Copies of the certified copies of the application from the International But * See the attached detailed Office action for a	ments have been received. ments have been received in priority documents have bee ureau (PCT Rule 17.2(a)).	Application No n received in this National Stag	e
_	hment(s) Notice of References Cited (PTO-892)	∆ \□	Summery /PTO 442)	
1) 2)	Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948)		Summary (PTO-413) o(s)/Mail Date	
3) 🔲	Information Disclosure Statement(s) (PTO-1449 or PTO/SI Paper No(s)/Mail Date		Informal Patent Application (PTO-152)	

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DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1, 2, 6 and 8 are rejected under 35 U.S.C. 102(b) as being anticipated by Novak et al. 5,623,853. Novak et al. discloses a first Y direction actuator having a stator 20 and a movable element 22b wherein the stator is driven by a second X direction actuator in a direction to suppress rotation of the stator 20 as described in Novak et al. column 16 lines 8-24.

In regard to claim 2, see Novak et al. column 15 lines 59-64.

In regard to claim 6, see Novak et al. column 15 lines 59-64 and see column 15 lines 28-36. The manipulated variable is the output of the position measuring system.

In regard to claim 8, the reaction force is the force that cause stator 20 to yaw. When linear motors 110a, 110b are driven to counteract the yaw, they cause the stator to absorb the reaction force.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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Claims 9 and 10 rejected under 35 U.S.C. 103(a) as being unpatentable over Novak et al. in view of Nishi 6,396,568 B1. Novak et al. teaches that his device is for microlithography in column 1 lines 12 and 13 and discloses exposure in column 1 line 20. The additional details present in claims 9 and 10 such as applying a photosensitive material onto a resist and using an optical system to irradiate the photosensitive material are details of a microlithography system. See Nishi column 1 lines 7 ½ -12 ½ where a general description of a photolithography process is given. Photolithography for semiconductors is what Novak et al. is calling microlithography. Instead of using the word "master" used by applicant in claim 9, Nishi mentions transferring a mask pattern. The mask pattern is the master. Nishi mentions "a photosensitive substrate" in lines 8 and 9 of column 1 and mentions "photoresist coated on wafer (W)" in column 1 line 36 ½. In column 1 lines 15 ½ to 19 ½ Nishi states that the wafer coated with photoresist forms the photosensitive substrate. The step of applying a photosensitive material on a substrate is implied in the Nishi reference and is inherent. The developing step present in applicant's claim 10 is mentioned in Nishi column 1 38 1/2 to 40 1/2. Nishi does not use the word "irradiate." Nishi states "exposes the photoresist coated on wafer (W) under the illumination light." This exposure is the irradiation step. Since Nishi and Novak et al. are from the same field of endeavor it would have been obvious at the time the invention was made for one of ordinary skill in the art to have utilized Nishi to supply details on the microlithography method that were not provided in Novak et al.

Allowable Subject Matter

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Claims 3-5 and 7 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

The following is a statement of reasons for the indication of allowable subject matter:

The prior art of record does not disclose or teach controlling a second actuator on the basis of acceleration of a movable element as recited in claim 3. Novak et al. mentions acceleration in column 10 lines 55-58 and states that the counter force from acceleration of the movable element 22b is not transferred to the beam 20 (the stator of the first actuator). Thus Novak et al. does not control the second actuator on the basis of acceleration. The prior art of record does not disclose or teach anything about the barycenter of the stator in combination with the other features of claim 7.

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Shiraishi 5,335,044 teaches 4 different exposure methods, with the barycenter being a part of the 4th method. Pastor 6,279,490 B1 shows a first actuator 10 and a second actuator 8 with the stator of 1st actuator driven by the second actuator. Pastor is concerned with yaw but in the Pastor device element 12 is rotated to counter-act yaw.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Judson H. Jones whose telephone number is 571-272-2025. The examiner can normally be reached on 8-4:30 M-F.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Darren Schuberg can be reached on 571-272-2044. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Judson Jones 4/13/2005

DARREN SCHUBERG SUPERVISORY PATENT EXAMINER TECHNOLOGY CENTER 2800